

EAST - [2539A.wsp:1]

File View Edit Tools Window Help

Active

- ✓ L1: (1151) "OPC" and ((photo\$6 photomask photoresist mask resist) with imag\$3)
- ✓ L2: (529) 1 and ((photo\$6 photomask photoresist mask resist) with pattern\$3)
- ✓ L3: (429) 2 and (imag\$3 with pattern\$3)
- ✓ L4: (158) 2 and (transparent with pattern\$3)
- ✓ L5: (296) 3 and ((transparent transfer\$3) with pattern\$3)
- ✓ L6: (43) 5 and (overlap\$3 with pattern\$3)

Failed

Saved

- ✓ (0) 10/672539
- ✓ (476) "OPC" with (photo\$6 photomask photoresist)
- ✓ (260) ("OPC" with (photo\$6 photomask photoresist)) and pattern\$4
- ✓ (185) (((("OPC" with (photo\$6 photomask photoresist)) and pattern\$4) and (substrate wafer)
- ✓ (76) (((("OPC" with (photo\$6 photomask photoresist)) and pattern\$4) and (substrate wafer)) and tr...
- ✓ (19) (((("OPC" with (photo\$6 photomask photoresist)) and pattern\$4) and (substrate wafer)) and t...
- ✓ (366328) "11" and ("OPC" photo\$6 photomask photoresist)
- ✓ (19) (((("OPC" with (photo\$6 photomask photoresist)) and pattern\$4) and (substrate wafer)) and...
- ✓ (612) "OPC" and ((photo\$6 photomask photoresist) with (substrate wafer))
- ✓ (804) "OPC" and ((photo\$6 photomask photoresist mask resist) with (substrate wafer))
- ✓ (685) ("OPC" and ((photo\$6 photomask photoresist mask resist) with (substrate wafer))) and ((pho...
- ✓ (233) (("OPC" and ((photo\$6 photomask photoresist mask resist) with (substrate wafer))) and ((ph...
- ✓ (44) (("OPC" and ((photo\$6 photomask photoresist mask resist) with (substrate wafer))) and ((pho...

Favorites

	Type	Hits	Search Text	DBs	Time Stamp	Com
1	BRS	0	10/672539	USPAT; US-PGPUB	2004/04/06 12:00	
2	BRS	476	"OPC" with (photo\$6 photomask photoresist)	USPAT; US-PGPUB	2004/04/06 14:12	

Start 8:04 AM



EAST - [2539A.wsp:1]								
File View Edit Tools Window Help								
L6: (43) 5 and (overlap\$3 with pattern\$3)								
Unlabeled								
	U	1	Document ID	Issue Date	Pages	Title	Current OR	Current XRef
15	<input type="checkbox"/>	<input type="checkbox"/>	US 20020051566 A1	20020502	10	Defect inspection apparatus and method	382/151	
16	<input type="checkbox"/>	<input type="checkbox"/>	US 20020045134 A1	20020418	39	Fabrication method of semiconductor integrated circuit device	430/311	430/396; 430/945
17	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 20020028391 A1	20020307	49	Method for formation of semiconductor device pattern, metho	430/5	430/311; 430/312;
18	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 20020004175 A1	20020110	17	Generic phase shift masks	430/5	430/322; 430/323;
19	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 20010049811 A1	20011206	31	Pattern distortion correction device, pattern distortion correction method,	716/4	716/21; 716/5
20	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6711732 B1	20040323	14	Full sized scattering bar alt-PSM technique for IC manufacturing in sub	716/19	716/21
21	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6709792 B2	20040323	46	Method for formation of semiconductor device pattern, metho	430/5	430/30; 430/311
22	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6706453 B2	20040316	46	Method for formation of semiconductor device pattern, metho	430/5	430/311
23	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6703167 B2	20040309	16	Prioritizing the application of resolution enhancement techniques	430/5	
24	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6686108 B2	20040203	38	Fabrication method of semiconductor integrated circuit device	430/30	430/22; 430/311
25	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6656646 B2	20031202	26	Fabrication method of semiconductor integrated circuit device	430/5	430/22; 430/30;
26	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6635393 B2	20031021	26	Blank for alternating PSM photomask with charge dissipation layer	430/5	430/311; 716/19
27	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6632576 B2	20031014	14	Optical assist feature for two-mask exposure lithography	430/5	430/394
28	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6605411 B2	20030812	47	Method for formation of semiconductor device pattern, metho	430/311	430/312; 430/394;
29	<input type="checkbox"/>	<input type="checkbox"/>	US 6602728 B1	20030805	12	Method for generating a proximity	438/16	438/14;

EAST - [2539A.wsp:1]								
File View Edit Tools Window Help								
L6: (43) 5 and (overlap\$3 with pattern\$3)								
Printed								
	U	1	Document ID	Issue Date	Pages	Title	Current OR	Current XRef
28	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6605411 B2	20030812	47	Method for formation of semiconductor device pattern, metho	430/311	430/312; 430/394;
29	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6602728 B1	20030805	12	Method for generating a proximity model based on proximity rules	438/16	438/14; 716/19;
30	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6479196 B2	20021112	15	Generic phase shift masks	430/5	
31	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6466304 B1	20021015	35	Illumination device for projection system and method for fabricating	355/71	355/67; 355/77
32	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6455203 B1	20020924	18	Mask structure and method of manufacturing the same	430/5	430/394
33	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6322934 B1	20011127		Method for making integrated circuits including features with a relatively sm	430/5	
34	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6320648 B1	20011120		Method and apparatus for improving pattern fidelity in diffraction-limited i	355/67	355/53; 355/77
35	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6316163 B1	20011113		Pattern forming method	430/296	430/30
36	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6303251 B1	20011016		Mask pattern correction process, photomask and semiconductor integr	430/5	430/30; 430/9
37	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6287732 B1	20010911		Generic phase shift masks	430/5	
38	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6251549 B1	20010626		Generic phase shift mask	430/11	430/311; 430/5
39	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6148158 A	20001114		Image processing apparatus and method having a plurality of image for	399/39	358/519; 358/521
40	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6077310 A	20000620	57	Optical proximity correction system	716/19	430/30
41	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 5879844 A	19990309	56	Optical proximity correction method	430/30	430/296; 430/942
42	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 5827623 A	19981027	24	Optical proximity correction halftone	430/5	